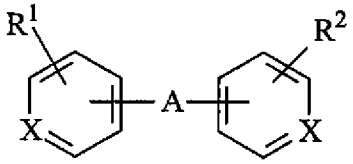
AMENDMENTS TO THE CLAIMS

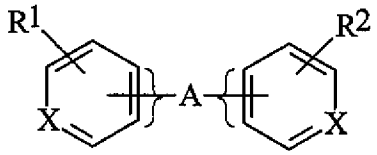
1. (Currently amended) A negative type resist composition comprising [alkali soluble resin,] polyvinyl phenol-based resin in which the phenolic hydroxyl group is partially alkyl-etherified, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)



(I)

wherein, A represents a sulfide group or disulfide group [or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, sulfide group, or disulfide group], X represents a nitrogen atom [or $C(NH_2)$], and R^1 and R^2 independently represent hydrogen or alkyl-[provided that, when X represents $C(NH_2)$, A represents sulfide group or disulfide group].

2. (Original) The negative type resist composition according to claim 1, wherein the basic compound of the formula (I) is represented by the following formula (Ia):



(Ia)

wherein, A, X, R^1 and R^2 are the same as defined in claim 1, and the marks, "}" and "{", indicate that A is positioned on 3-position, or 4-position on the six-membered rings with respect to X.

3. (Canceled)

4. (Canceled)

5. (Canceled)

6. (Canceled)

7. (Previously Presented and Amended) The negative type resist composition according to [claim 6] claim 1, wherein the basic compound of formula [Ib] (I) is selected from 4,4'-dipyridylsulfide and 4,4'-dipyridyldisulfide.

8. (Canceled)

9. (Original) The negative type resist composition according to claim 1, wherein the acid generator is a sulfonic ester of N-hydroxyimide compound.

10. (Currently Amended) The negative type resist composition according to claim 1, 2, 7, or 9, wherein composition ratio of the basic compound of formula (I) is between 0.02 and 1 wt %, based on the total solid content in the composition.

11. (Cancelled)

12. (Cancelled)

13. (Cancelled)